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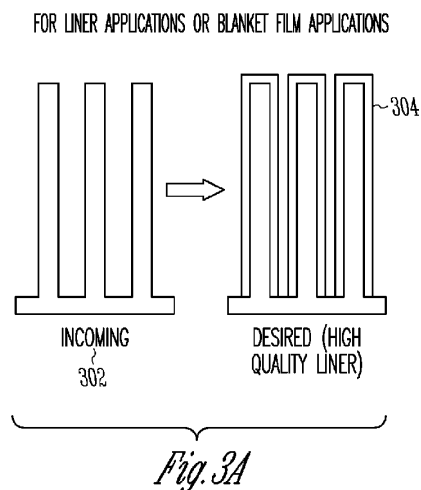
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(54) Title: IN-SITU FILM ANNEALING IN SUBSTRATE PROCESSING



(57) Abstract: In one example, a method for depositing a film on a sub-
strate comprises arranging a substrate on a substrate support in a process-
ing chamber and setting a processing pressure, temperature and pressure
in the chamber. The method includes striking a plasma and depositing and
annealing the film on the substrate at a thickness in a predetermined film
thickness range.